

DEVELOPMENT OF A CONTINUOUS NUCLEAR DEMAGNETISATION REFRIGERATOR (CNDR)

S. Trigueneaux, J. Butterworth, G. Le Roy, S. Midlik, D.
Schmoranzler, A. Fefferman

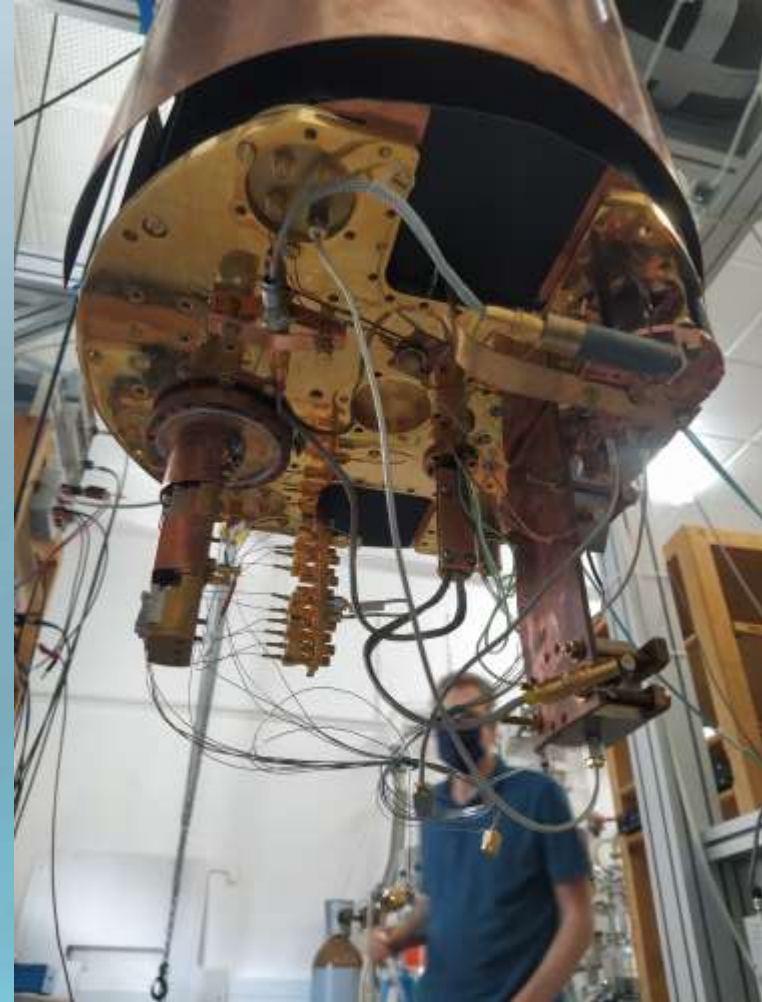


European Research Council



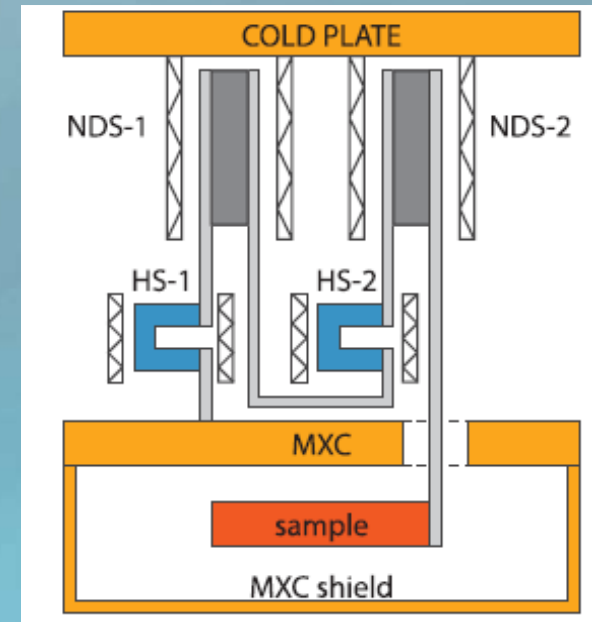
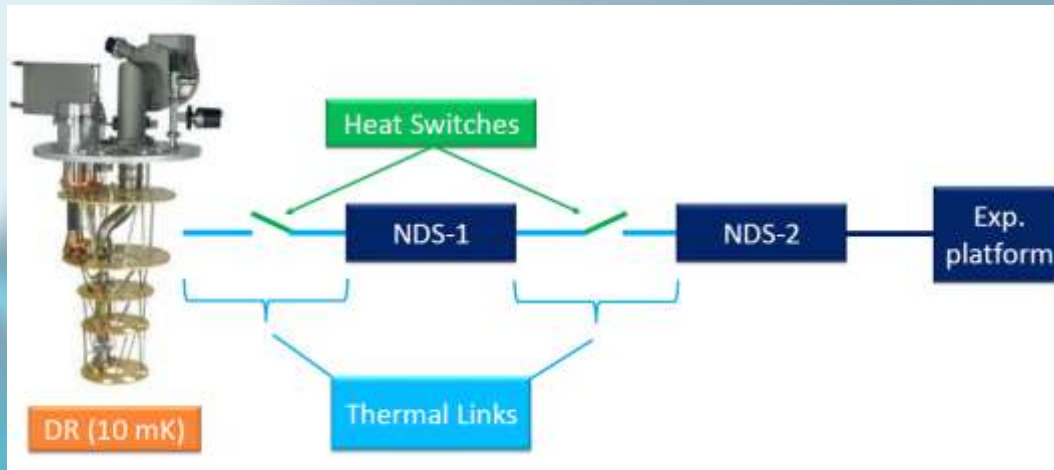


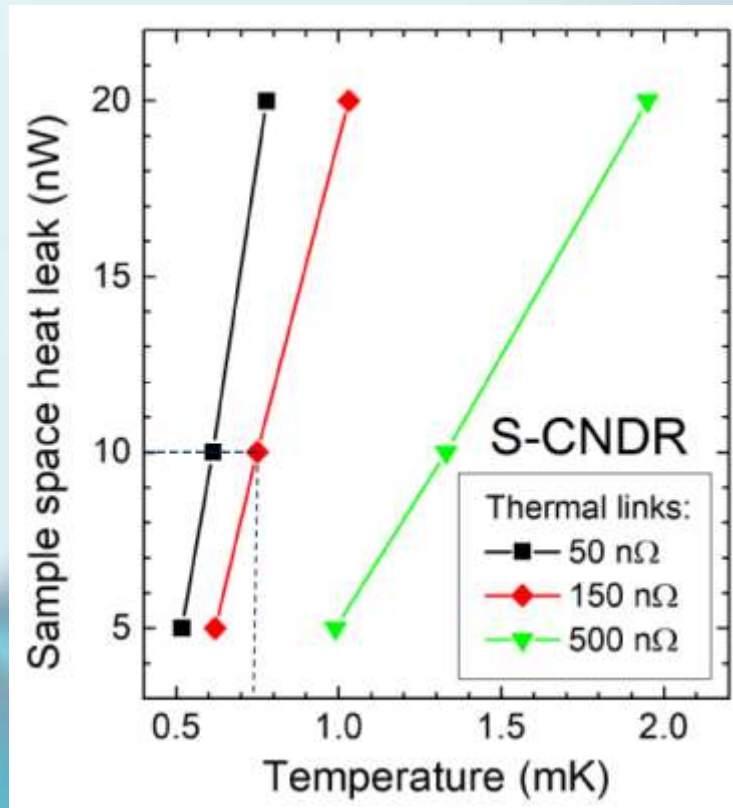
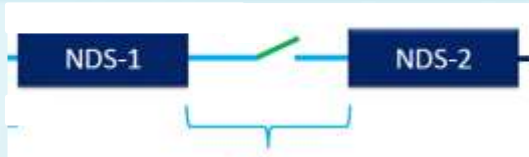
- Overview
- Thermal resistance issue
- Contact / Welding / Heat Switch issue
- Summary of resistance measurements so far
- Heat Switch thermal characterization: normal and SC states
- Test of the Heat Switch with a single NDS
- Conclusion





- Goal is to achieve 1 mK continuously
- Serial configuration is preferred to parallel (refer to David's talk)
 - Twice fewer heat switches
 - More compact
 - Second stage (Nuclear Demag Stage 2 - NDS2) with lower fields



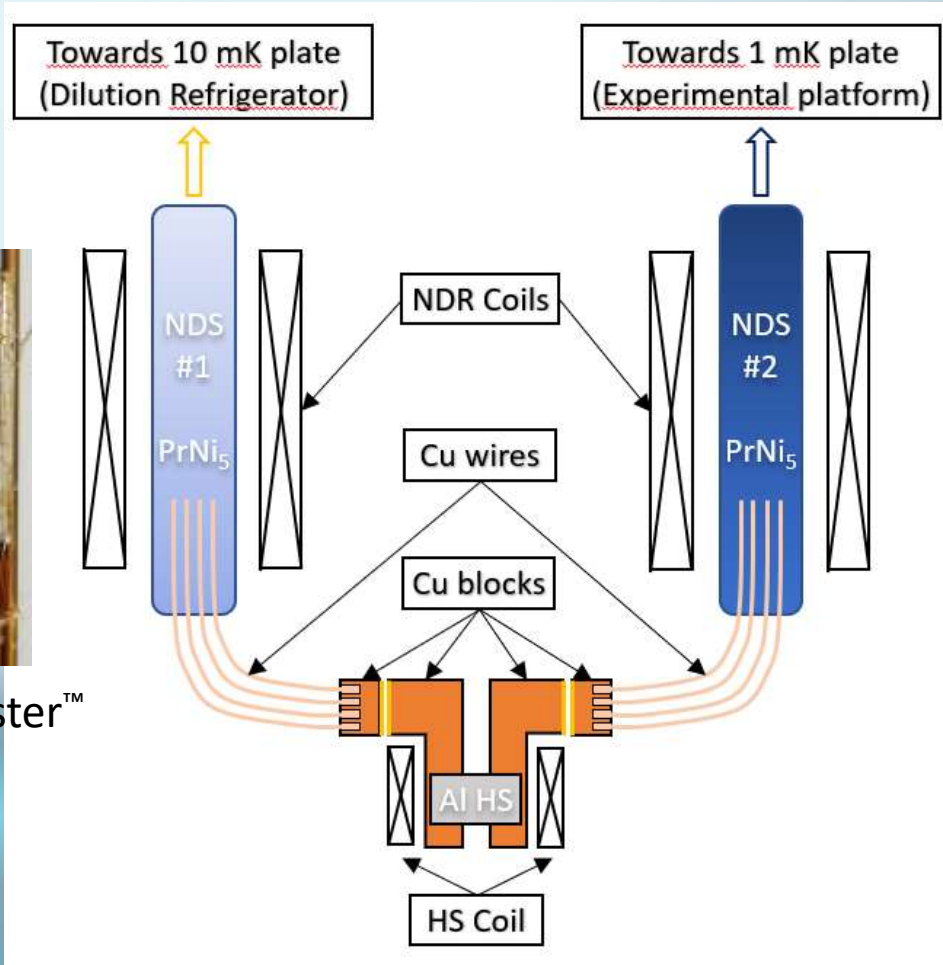


D. Schmoranzer *et al.*,
Cryogenics **110**, 103119 (2020).

- In S-CNDR, performance is limited by the thermal resistance between the 2 NDSs (\Leftrightarrow electrical R using the Wiedemann-Franz law)
- 10 nW heat load (typ. 5 nW residual losses) and 150 nΩ \Rightarrow \sim 750 μ K operating T according to simulations
- With some margin, we give ourselves a goal of 150 nΩ
- Minimizing R will be helpful, even in a parallel configuration



Lancaster™



15 individual contributors:

- Bulk materials
- **Contacts / Assemblies**

NDS to Cu wires

Cu wires

Cu wires to Cu block

Cu block (dismountable)

Cu blocks connection

Cu block (HS assembly)

Cu block to Al heat HS

----- Al HS -----



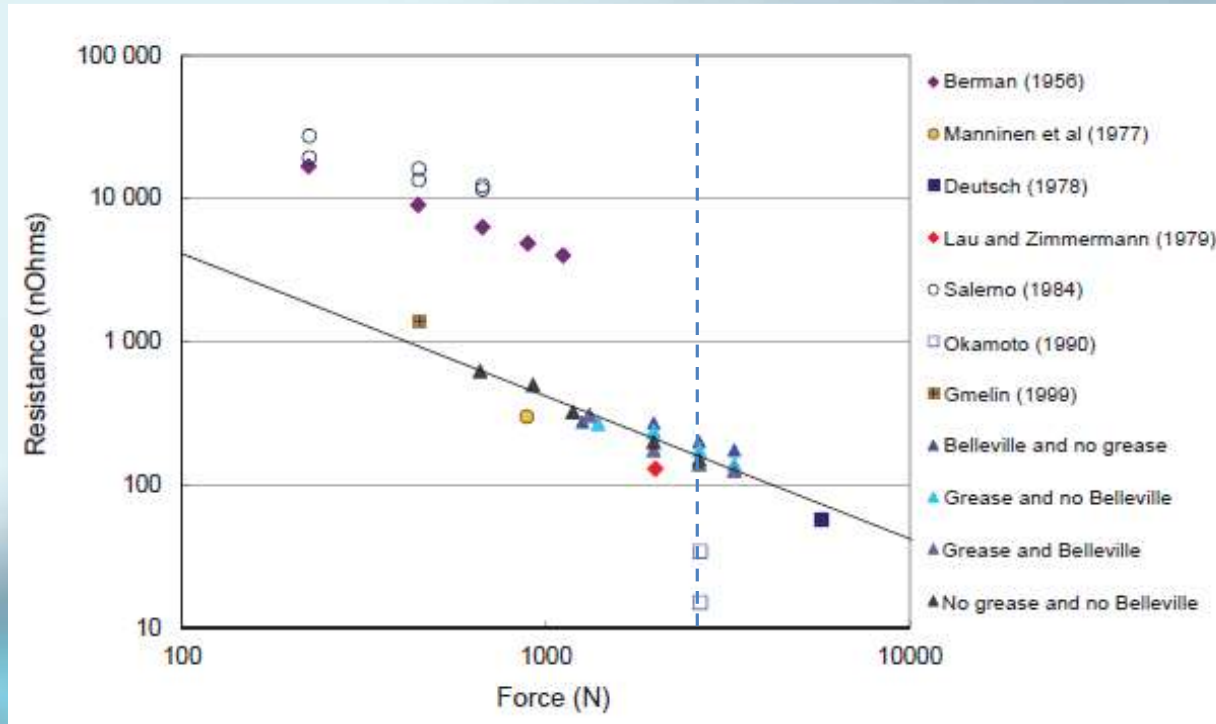
Label	Type	R (nΩ)	#	Notes
NDS to Cu wires	Brazed	5	2	10 wires => 50 nΩ per wire allowed
Cu wires	Bulk	30	2	For 10 Wires ϕ 1.5 mm - L=8 cm - RRR 2500
Cu wires to Cu block	Welded	5	2	10 wires => 50 nΩ per wire allowed
Cu block (dismountable)	Bulk	5	2	Cu with RRR > 1 000
Cu blocks connection	Pressed	10	2	Goal
Cu block (HS assembly)	Bulk	5	2	Cu with RRR > 1 000
Cu block to Al heat HS	Pressed	10	2	Goal
Al HS	Bulk	5	1	Calculated 2 nΩ with RRR = 5000
TOTAL		145		

Major **uncertainties** = contact resistances

Most critical one = **Al to Cu**



- Is it possible to make a Cu-Cu or Cu-Al joint with a contact res. (R_c) in the $n\Omega$ range ?



Review of Cu-Cu contacts

F. Blondelle *et al.*, *Journ. Low Temp. Phys.* **175**, 877 (2014).

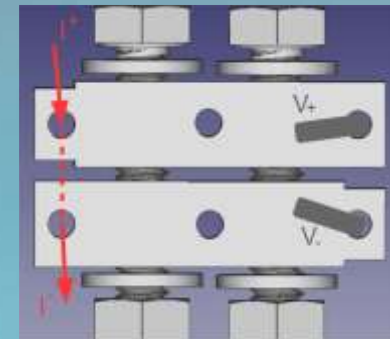
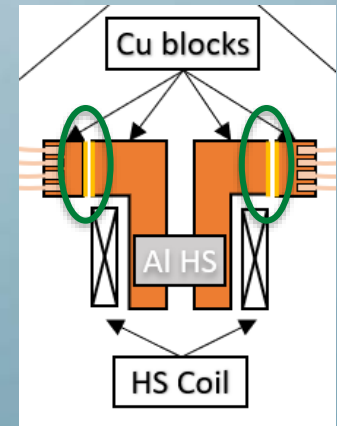
- For Cu-Cu contacts at 3 kN (M4 compatible), R_c usually > 100 n Ω . Some authors report $R_c < 10$ n Ω including for Cu-Al contacts.



Goal: dismountable Cu-Cu joint
 Simple design for preliminary tests

Parameters:

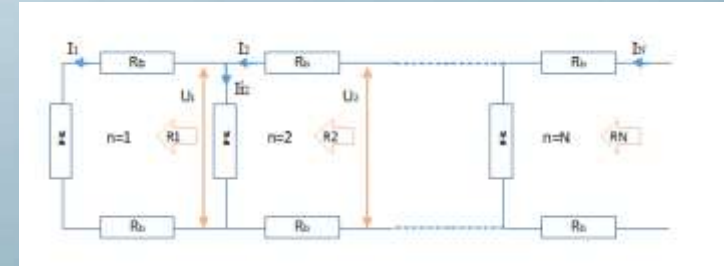
- Rough Polish (RP \Leftrightarrow P800) or fine polish (P \Leftrightarrow P2000)
- Coating (Ag or Au) or not
- Electro (Ag + Au) or electroless (Ag) plating or evaporation (Au)
- Application of extra compression force (7.5 kN) or not



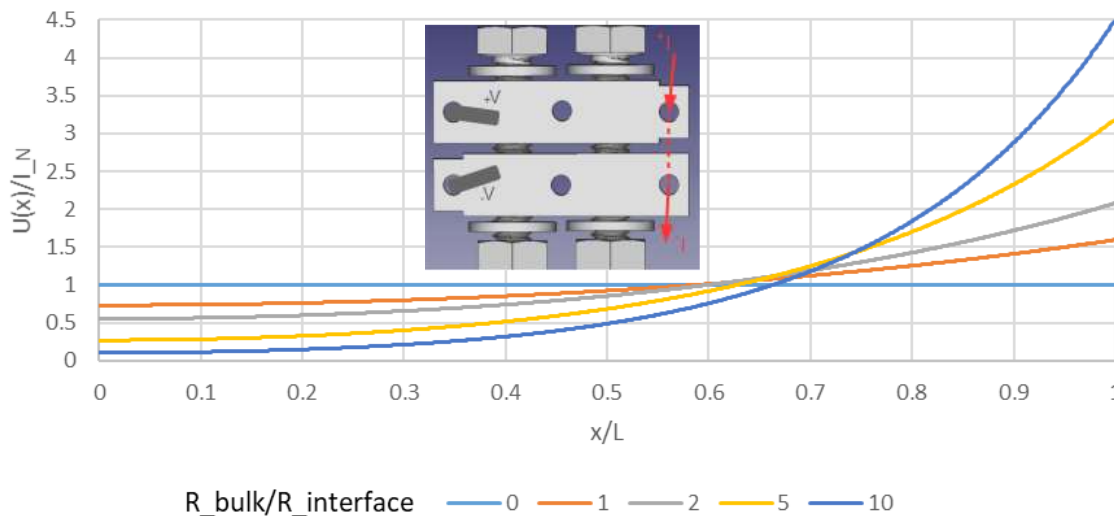


Notes:

- Use of high RRR bulk Cu is mandatory
- 4 wire measurements can be tricky



Resistance ladder network



Apparent R as function of V pickups position for various $R_{bulk} / R_{contact}$ ratios

Current injected at $x/L = 1$

- Our measurements ($x=0$ and $x=0.5$) showed no discrepancy at 4.2 K



Results:

Sample	R at 4K	Sample	R at 4K
Cu-Cu RP 7.5 kN	$435 \pm 7 \text{ n}\Omega$	Au Dalic P	$5.5 \pm 8.4 \text{ n}\Omega$
✓ Au Dalic RP	$3.9 \pm 6.1 \text{ n}\Omega$	Au Evap P	$13.7 \pm 8.7 \text{ n}\Omega$
Ag Dalic RP	$5.2 \pm 5.6 \text{ n}\Omega$	Cu-Cu RP	$44 \pm 9 \text{ n}\Omega$
Electroless Ag RP	$47 \pm 9 \text{ n}\Omega$		

- Extra compression not recommended
- Rough polish is sufficient
- Dalic electro plating provides the best results. Au preferred to Ag
- Below 50 nΩ feasible for Cu-Cu contacts with no coating or a simple electroless coating



Impact of multiple connections / disconnections:

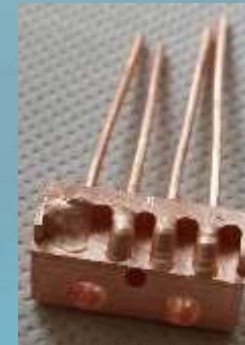
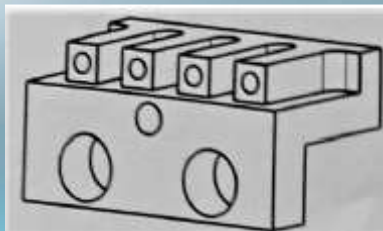
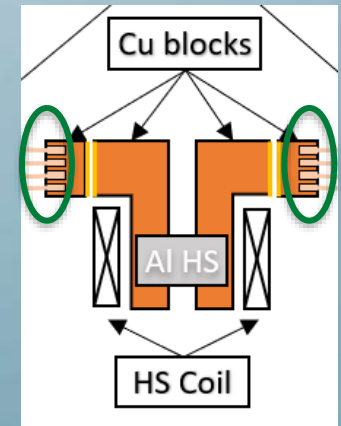
	RP AuDalic	RP AgDalic	P AuDalic
Dismounted+0 09/12/20	$3.9 \pm 6n\Omega$	$5.2 \pm 6n\Omega$	$5.5 \pm 8n\Omega$
Dismounted+2 10/06/21	$6.7 \pm 7.2n\Omega$	$5.7 \pm 6n\Omega$	$8 \pm 7n\Omega$
Dismounted+3 18/06/21	$5.5 \pm 14n\Omega$	$5 \pm 10n\Omega$	$3.9 \pm 14n\Omega$
Dismounted+0 23/06/21	$4.7 \pm 7n\Omega$	$4.7 \pm 5.3n\Omega$	$7.1 \pm 5.3n\Omega$
Dismounted+1 *air 30/07/21	$2.8 \pm 3.3n\Omega$	$8.9 \pm 3.9n\Omega$	$6.9 \pm 3.4n\Omega$

No measurable change in 6 months including after 1 month with the 2 parts in contact with air



Goal: low resistivity Cu wire to Cu block assembly

Selected design for a 4 wire assembly after a series of basic tests:





Results:

Sample	After Annealing & Heat treatment				
	Resistance at 4K for 1 weld [$n\Omega$]				4-wire resistance [$n\Omega$]
	weld n°1	weld n°2	weld n°3	weld n°4	
CuCuWeld7	59 ± 8	69 ± 7	39 ± 17	52 ± 17	13.1 ± 3.6
CuCuWeld8	21 ± 18	32 ± 7	22 ± 14	29 ± 9	6.3 ± 3.5



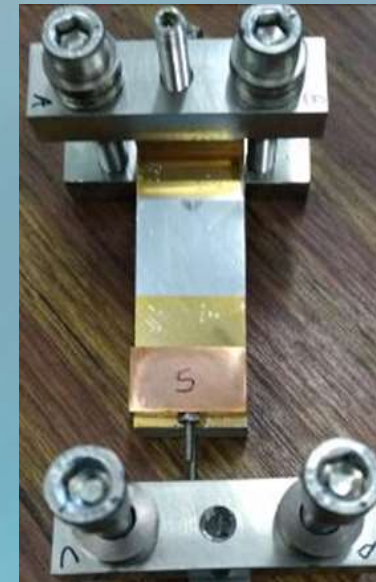
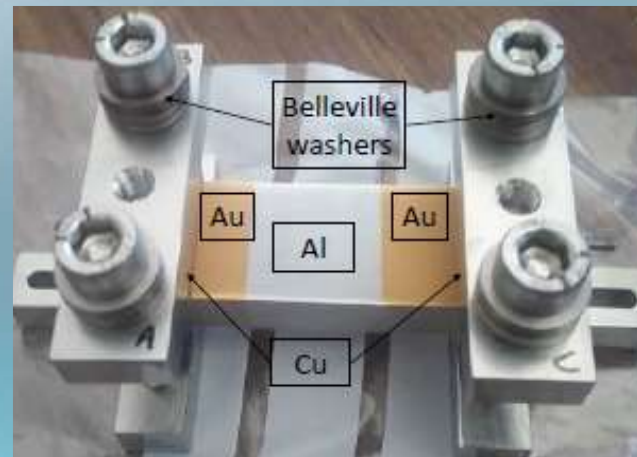
- Up to 50% discrepancy between the different welds
- Resistances are comparable to that of the bulk material => no major contribution of the welding process
- Global R in agreement with our needs



Idea (inspired from Shigematsu): chemical etching followed by plasma etching + e-beam Au deposition (evaporation)

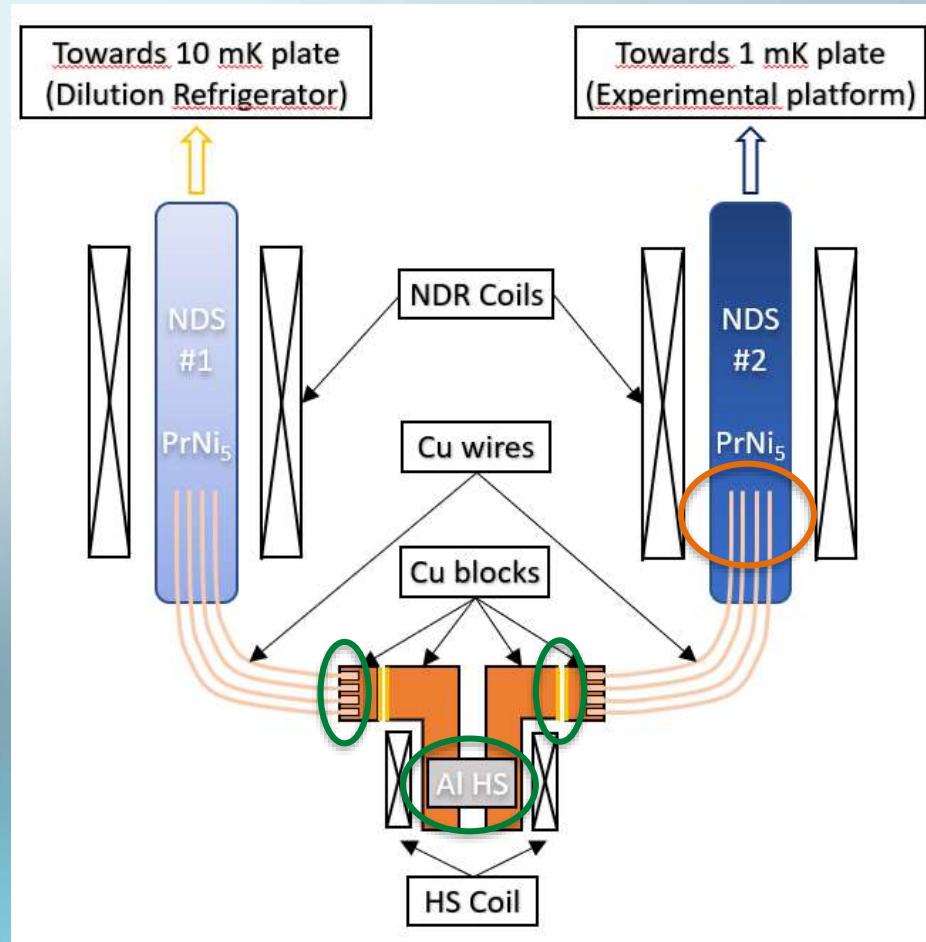
- Preliminary tests on a basic Al to Cu assembly:
- Different configurations tested (cf. article)

S. Triqueneaux *et al.*,
Journ. Low Temp. Phys.
203, 345 (2021)



- Contact resistance as low as **3 nΩ** at 4.2 K could be achieved





Most of the contact resistances are validated



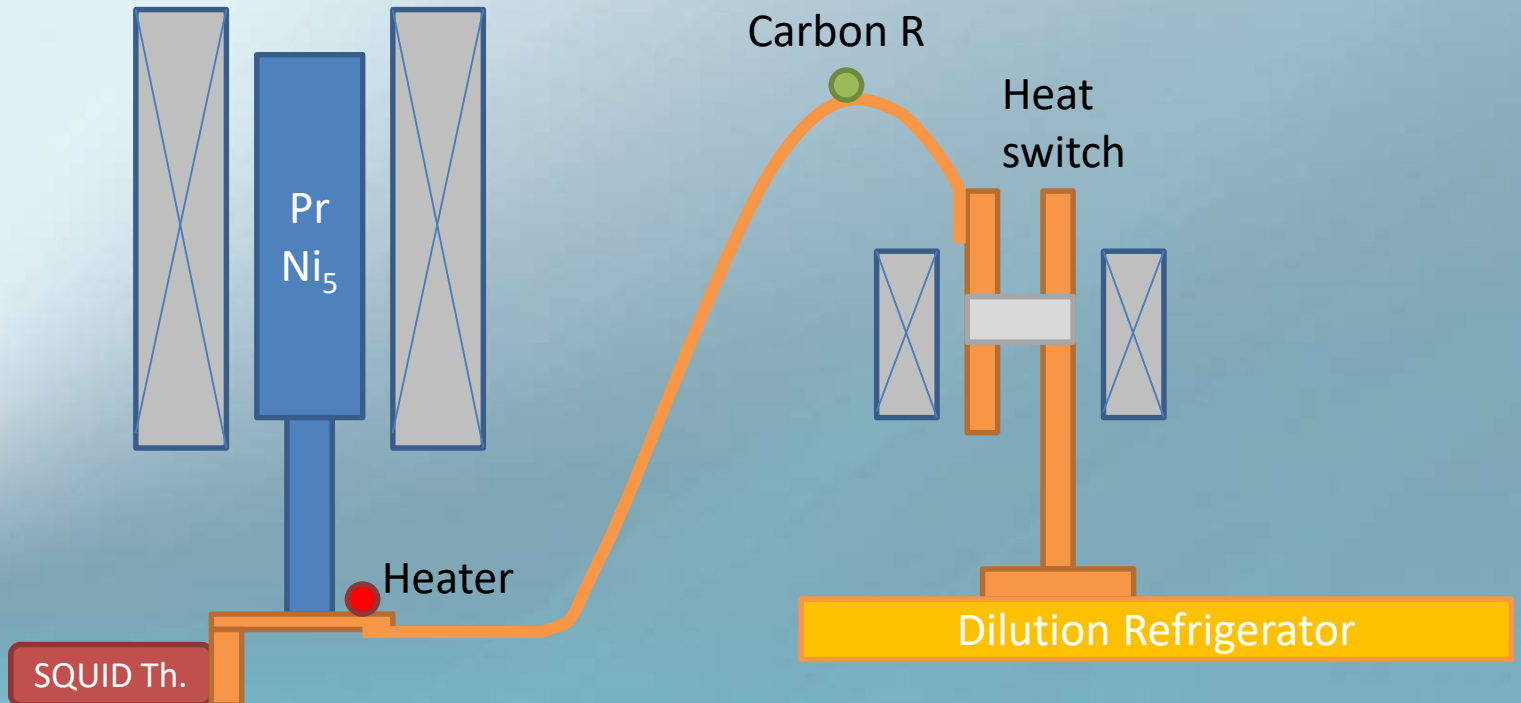
Label	Type	R (nΩ)	#	Notes
NDS to Cu wires	Brazed	5	2	Same as ini
Cu wires	Bulk	30	2	Same as ini
Cu wires to Cu block	Welded	5	2	Measured (~ 50 nΩ per weld)
Cu block (dismountable)	Bulk	2	2	Measured
Cu blocks connection	Pressed	5	2	Measured
Cu block (HS assembly)	Bulk	3	2	Measured
Cu block to Al heat HS	Pressed	1	2	Measured
Al HS	Bulk	1	2	Measured (3 nΩ equivalent R)
TOTAL		103 ✓		

Relaxes some constraint on the wires

NDS to wires contact R to be validated



Further step = HS combined to a single NDS:



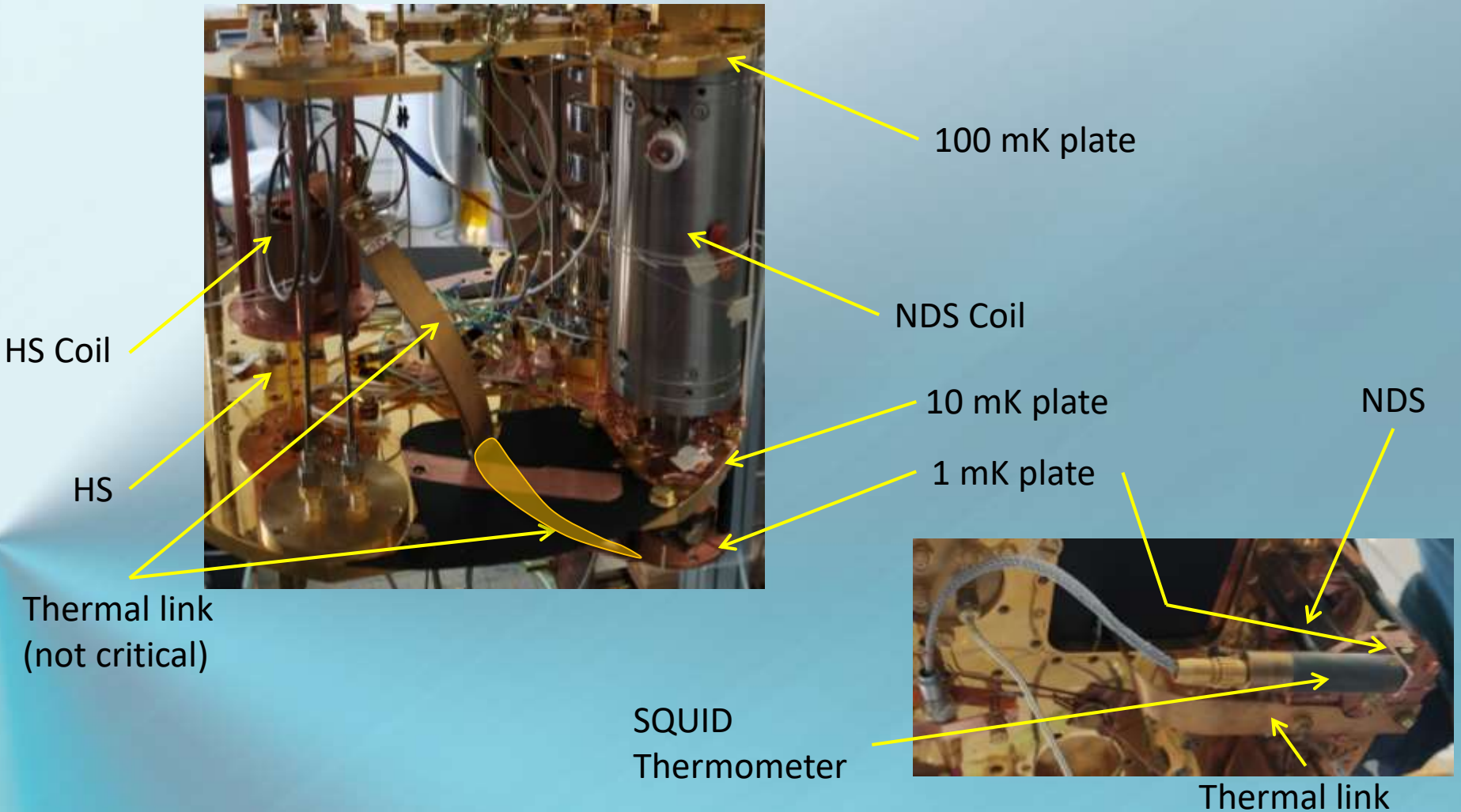
Existing PrNi_5 stage (**Parpia**)

PrNi_5 thermalized onto an Ag rod via cadmium soldering



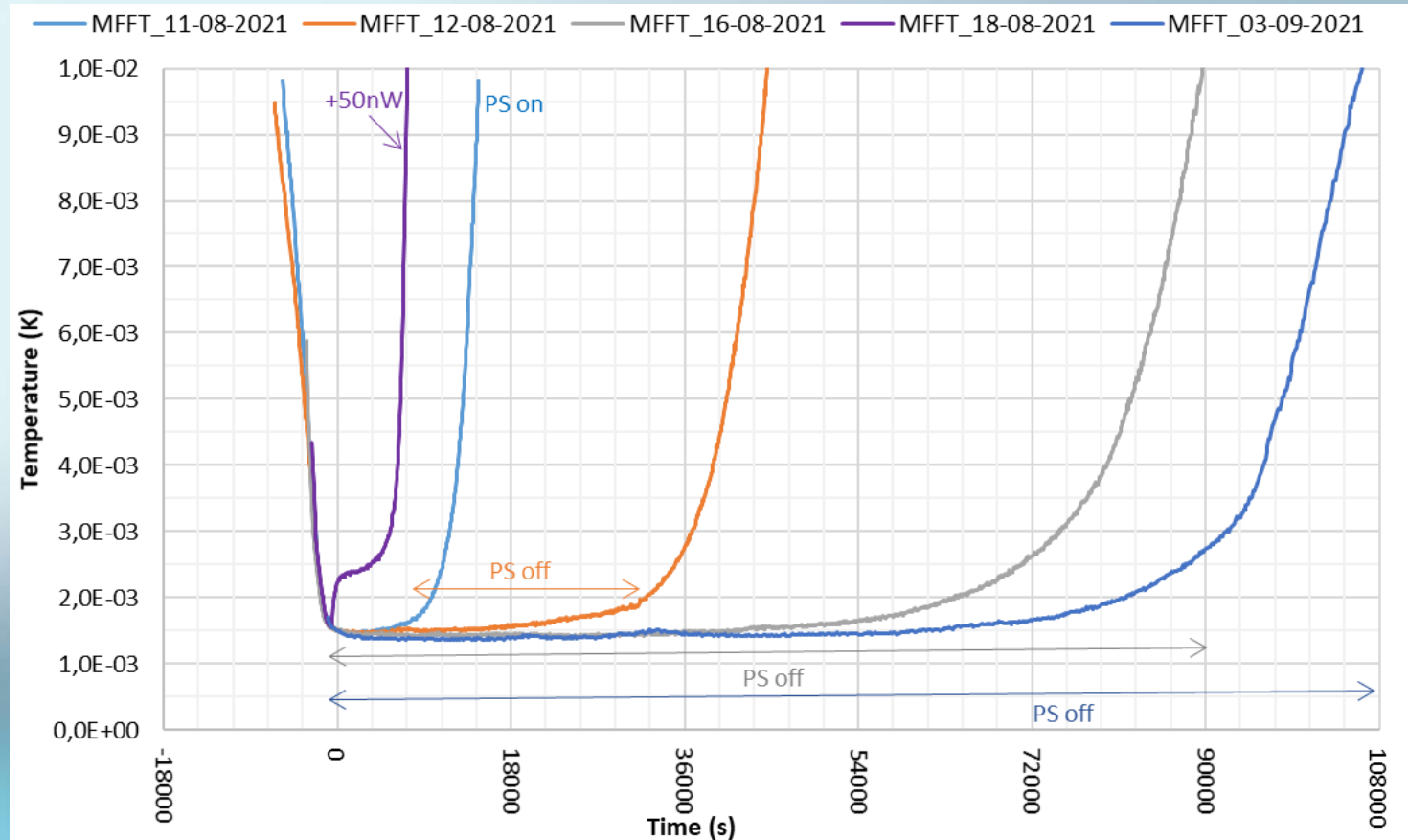


Once mounted onto Andrew's (Bluefors) DR:





Results:



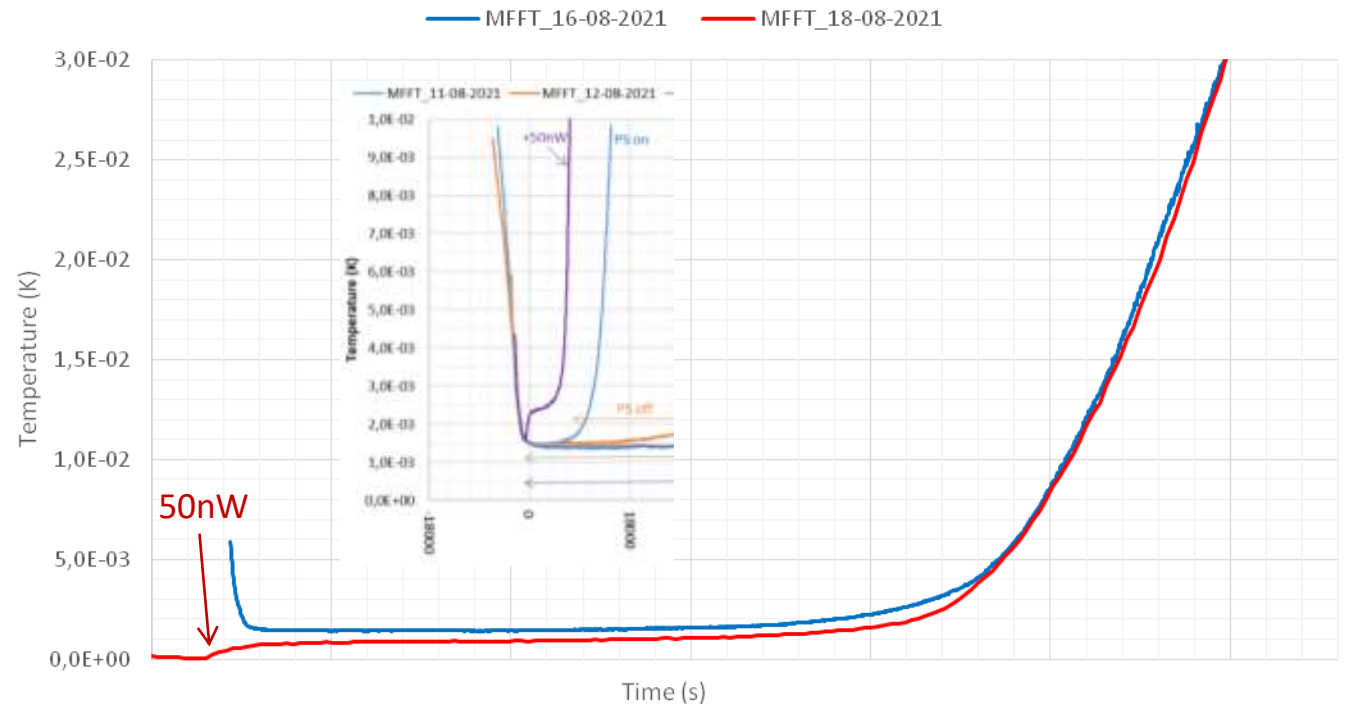
- Power Supply (PS) has huge parasitics at 0 current!
- Best case : ~23 hours with the SQUID therm. displaying $T < 2$ mK



Results:

Hypothesis: SQUID noise thermometer saturates at $\sim 1.45\text{mK}$

50nW heat applied to MFFT_18: Time axis is expanded by factor 12 for MFFT_18
 MFFT_18 is adjusted downwards by 1,5mK to account for T offset caused by heat flow



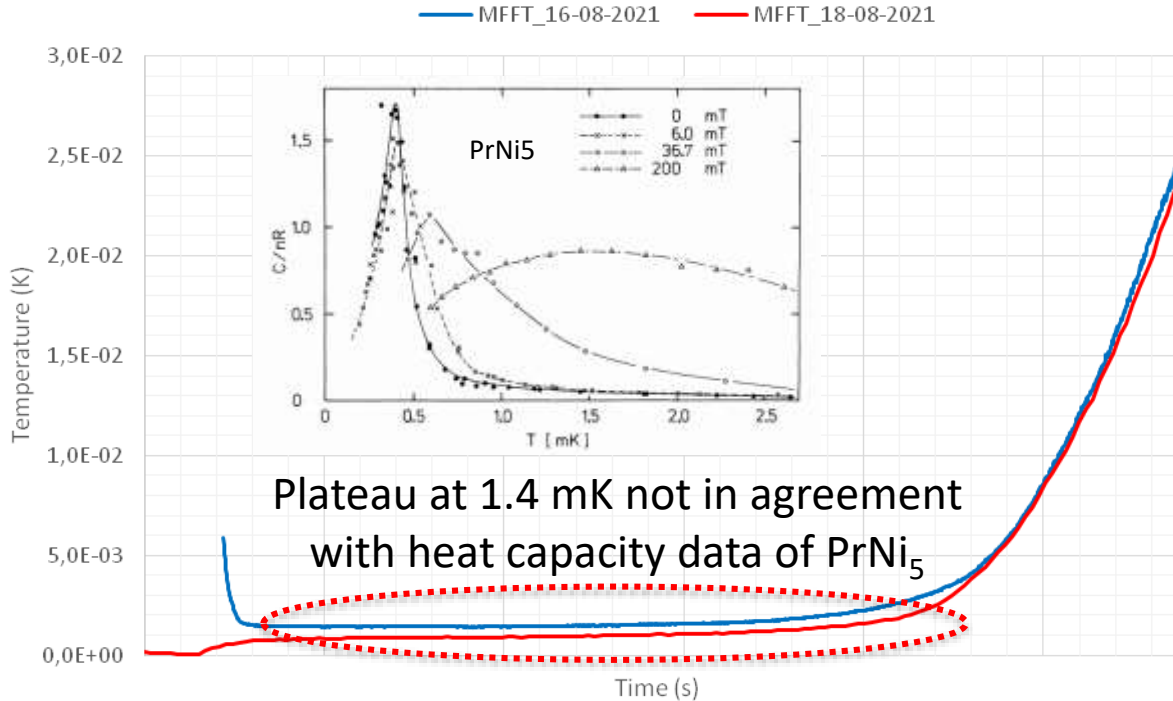
- Increase by a factor ~ 12 of total heat load when 50 nW heat is applied. This would imply parasitics of ~ 4.5 nW (OK with previous publications)
- Best case (23 hours) may suggest variable parasitics & as low as ~ 2 nW



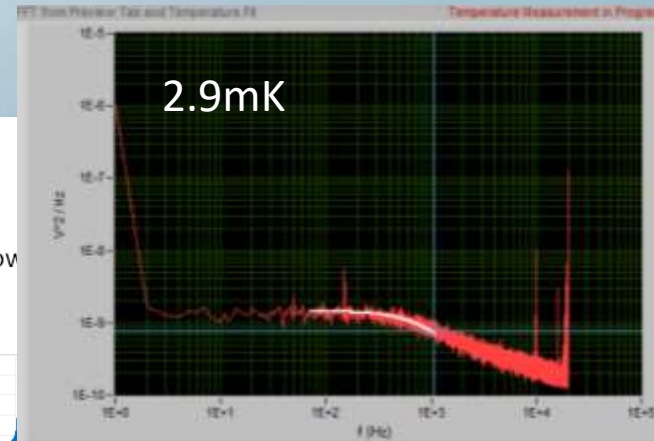
Results:

Hypothesis: SQUID noise thermometer saturates at ~1.45mK

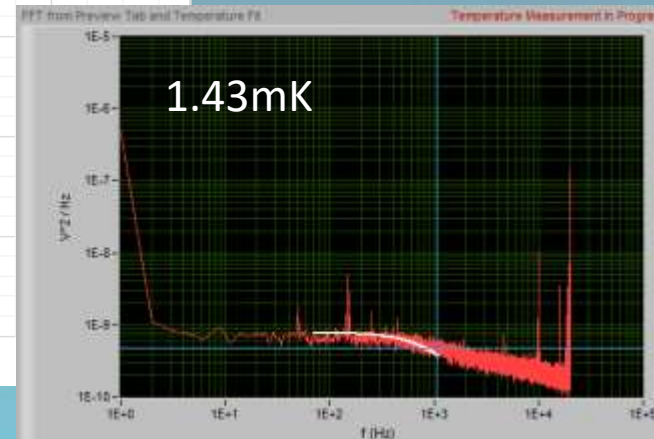
50nW heat applied to MFFT_18: Time axis is expanded by factor 12 for MFFT_18
 MFFT_18 is adjusted downwards by 1,5mK to account for T offset caused by heat flow



Plateau at 1.4 mK not in agreement with heat capacity data of PrNi₅



SQUID Therm. behavior is under Analysis





- Most of the thermal resistance issues are solved
- The heat switch has demonstrated very good performance, including with an NDS
- We believe that we have been able to reach below 800 μK on a PrNi_5 stage with 2-4 nW parasitics
- Still some optimizations needed: power supply, thermometry



We plan to focus our efforts on the design and manufacture of our own NDS

- Manufacturing issue for PrNi_5
 - Thermal contact issue (Cd not very convenient)
- => Overall PrNi_5 to Cu thermal contact might become the bottleneck
- Al less efficient
 - Al – Cu contact should not be an issue
 - Al not adapted to serial configuration